

ABSTRACT OF THE DISCLOSURE

A method of preparing a file that stores layout of devices to be created with photolithography for optical and process correction (OPC). Polygons that define structures to be created are initially fragmented into edge segments and a simulation of
5 how the edge segments will be printed under process conditions is performed. The results of the simulation are used to adjust/refragment the edge segments. In one embodiment, the curvature of light intensity at the edge segments is used to adjust the fragmentation of the polygons.

10